

**RESPONSE UNDER 37 CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1794
Docket No.: 0001.1045**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Joo-Ho KIM et al.

Application No. 10/529,044

Group Art Unit: 1794

Confirmation No. 1715

Filed: January 17, 2006

Examiner: Kevin M. Bernatz

For: HIGH DENSITY RECORDING MEDIUM WITH SUPER-RESOLUTION NEAR-FIELD
STRUCTURE MANUFACTURED USING HIGH-MELTING POINT METAL OXIDE OR
SILICON OXIDE MASK LAYER

AMENDMENT AFTER FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Attention: **BOX AF**

Sir:

This is in response to the Office Action mailed May 19, 2009, and having a period for response set to expire on August 19, 2009. Because July 19, 2009 fell on a Sunday, this Amendment After Final Rejection is filed on Monday, July 20, 2009, in accordance with MPEP §710.05, so as to be considered as an Early Response under MPEP §714.13 filed within 2 months of the mailing date of the Final Office Action.

Reconsideration of the claims is respectfully requested. The following remarks are respectfully submitted.